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4. Title of the invention

Improved Vertical External Cavity Surface Emitting Laser

5. Name of your agent (if you have one)

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## 1 Improved Vertical External Cavity Surface Emitting Laser

.2

3 The present invention relates to an improved Vertical

4 External Cavity Surface Emitting Laser (VECSEL) and in

5 particular to a VECSEL that exhibits improved wavelength

6 tuning characteristics.

7

8 Diode-pumped VECSELs are an attractive format of

9. semiconductor laser known to those skilled in the art for

10 scientific, instrumentation and non-linear optics

Il applications. The design and fabrication of a VECSEL

12 laser with Circular TEMoo output beams has been described

13 by Kusnetsov et al (IEEE Journal of selected Topics in

14 Quantum Electronics Vol. 5, Page 561 - 573 (1999) "Design

15 and Characteristics of High-Power (>0.5W CW) Diode-Pumped

16 Vertical-External-Cavity Surface- Emitting Semiconductor

17 Lasers with Circular TEMoo Beams").

18

19 The optical gain medium within a VECSEL is provided by

20 the recombination of electrical carriers within very thin

21 layers of a semiconductor material. These layers are

22 generally termed quantum-well (QW) layers or active

1 layers exhibiting a typical thickness of around 150 Å or

2 less.

3

- 4 Application of intracavity spectral and temporal control
- 5 techniques such as picosecond and subpicosecond mode-
- 6 locking, single-frequency operation and intracavity
- 7 second-harmonic generation have also been demonstrated
- 8 see:
- 9 Garnache et al. Appl. Phys. Lett. Vol 80 Page 3892-3894
- 10 (2002) "Sub 500-fs Soliton-Like Pulse in a Passively
- 11 Mode-Locked Broadband Surface-Emitting Laser with 100mW
- 12 Average Power";
- 13 Holm et al. IEEE Photon. Technol. Lett. Vol 11 Page
- 14 1551-1553 (1999) "Actively stabilised Single-Frequency
- 15 Vertical-Cavity AlGaAs Laser"; and
- 16 Schiehlen et al: TEEE Photon. Technol. Lett. Vol 14
- 17 Page 777-779 (2002) "Diode-Pumped Semiconductor Disk
- 18 Laser With Intracavity Frequency Doubling using Lithium
- 19 Triborate (LBO)", respectively.

- 21 A significant limiting factor in all of the
- 22 aforementioned systems is that their output power is
- 23 greatly limited by the thermal response of the gain
- 24 structure. Typically, without employing thermoelectric
- 25 cooler (TEC) mounting techniques or cooling strategically
- 26 deployed heat sinks with chilled water, both of which are
- 27 well known to those skilled in the art, the output powers
- 28 at room temperatures are limited to a few 10's of mW.
- 29 The employment of these cooling methods act to improve
- 30 the output powers but are generally very inefficient due
- 31 to the fact that the heat must be removed from the gain :
- 32 medium via the substrate of the structure.

1 The prior art teaches of several methods for improving

- 2 the efficiency of VECSEL cooling systems. The first
- 3 involves growing the gain structure in reverse order,
- 4 mounting on a heatsink and etching away the substrate.
- 5 However, the resultant scattering due to poor surface
- 6 quality remains a significant problematic feature within
- 7 low gain lasers that usually tolerate only very little
- 8 losses (~2%).

9

- 10 Alford et al. described an alternative method for
- 11 removing heat from the gain region that involves no post-
- 12 growth alterations to the structure (see J. Opt. Soc. Am.
- 13 B Vol. 19, Page 663 (2002) "High Power and Good Beam
- 14 Quality at 980nm from a Vertical External-Cavity Surface-
- 15 Emitting Laser"). In particular this document teaches of
- 16 an InGaAs-based VECSEL that employs, in conjunction with
- 17 a thermoelectric cooler, a sapphire heatspreader
- 18 capillary bonded in optical contact with the epi-side (or
- 19 active surface) of the gain structure. More recently,
- 20 Hastie et al. have described a VECSEL that employs an
- 21 intracavity Silicon Carbide (SiC) heatspreader that is
- 22 optically contacted to the active surface of the gain
- 23 medium (see IEEE Photon. Technol. Lett. Vol 15 Page 894-
- 24 896 (2003) "O.5 W Single Transverse-Mode Operation of an
- 25 850nm Diode Pumped Surface-Emitting Semiconductor
- 26 Laser"). Generally, Silicon Carbide has been shown to
- 27 exhibit superior heat spreading characteristics than
- 28 heatspreaders comprising Sapphire.

- 30 In order to produce single frequency operation it is
- 31 known to those skilled in the art to incorporate
- 32 intracavity polarisation selecting elements such as
- 33 birefringent filters, orientated at Brewster's angle, and

l an etalon within the laser cavity. Wavelength scanning

2 can then be achieved via a number of known techniques

3 e.g. the incorporation of stabilisation to a side of a

4 transmission peak of an external reference cavity. Suc

5 techniques are currently employed to produce tuneable

5 Ti:Sapphire and Dye lasers that find particular

7 application in the field of high resolution spectroscopy.

8

9 It is known that the gain medium of a VECSELs possesses a

10 relatively high gain bandwidth that provides the

Il potential for a VECSEL to be tuned approximately 20 nm

12 either side of the engineered wavelength. However, in

13 practice it has been found that the above laser frequency

14 stabilisation and wavelength scanning techniques do not

15 lend themselves to be readily incorporated within the

16 described VECSELs. This is principally due to the fact

.17 that there is significant modulation of the output power

18 of the VECSEL as the laser's operating wavelength is

19 scanned (between 10 - 30%) due to the heatspreader acting

20 as an additional intracavity etalon. Furthermore, both

21 Sapphire and Silicon Carbide heat spreading elements are

22 found to interfere with the polarisation selection

23 properties of any intracavity birefringent filter thus

24 reducing the frequency stability and tuneability of the

25 cavity.

26

27 It is an object of aspects of the present invention to

28 provide a Vertical External Cavity Surface Emitting Laser

29 (VECSEL) that overcomes one or more of the limiting

30 features on frequency stability and wavelength tuning

31 associated with the VECSELs described in the prior art.

- 1 The term "active surface" used throughout the
- 2 specification in relation to one or more of the
- 3 intracavity elements of the VECSEL refers to that surface
- 4 on which the optical pumping field is initially incident.

- 6 According to a first aspect of the present invention
- 7 there is provided a Vertical External Cavity Surface
- 8 Emitting Laser comprising a wafer structure and a
- 9 heatspreader located at an active surface of the wafer
- 10 structure wherein the heatspreader comprises a non-
- ll birefringent material.

12

- 13 Preferably the heatspreader comprises an anti-reflection
- 14 coating located on an active surface of the heatspreader.

15:

- 16 According to a second aspect of the present invention
- 17 there is provided a Vertical External Cavity Surface
- 18 Emitting Laser comprising a wafer structure and a
- 19 heatspreader located at an active surface of the wafer
- 20 structure wherein the heatspreader comprises an anti-
- 21 reflection coating located on an active surface of the
- 22 heatspreader.

23

- 24 Preferably the heatspreader comprises a non-birefringent
- 25 material.

- 27 According to a third aspect of the present invention
- 28 there is provided a Vertical External Cavity Surface
- 29 Emitting Laser comprising a wafer structure and a
- 30 heatspreader located at an active surface of the wafer
- 31 structure wherein the heatspreader comprises a non-
- 32 birefringent material and an anti-reflection coating
- 33 located on an active surface of the heatspreader.

i

2 Preferably the anti-reflection coating is optimised for

3 efficient operation with a refractive index of the non-

4 birefringent material.

5

6 Preferably the active surface of the heatspreader

7 comprise a wedge.

8

9 Most preferably the heatspreader comprises a single

10 diamond crystal.

11

12 Preferably the laser further comprises an intracavity

13 polarisation selecting element that provides a first

14 means for selecting the operating wavelength of the

15 laser.

16.

17 Preferably the intracavity polarisation selecting element

18 comprises a birefringent filter orientated at Brewster's

19 angle.

20

21 Preferably the laser further comprises an intracavity

22 etalon that provides a second means for selecting the

23 operating wavelength of the laser.

24

25 Optionally the laser comprises a three mirror folded

26 cavity arrangement.

27

28 Preferably the laser further comprises an external

29 reference cavity that allows for the frequency

30 stabilisation of the laser output to a side of a

31 transmission peak of the external cavity.

-

- 1 Preferably the laser further comprises a cavity mirror
- 2 mounted on a first piezoelectric crystal and an output
- 3 coupler mounted on a second piezoelectric crystal wherein
- 4 the combined movement of the cavity mirror and the output
- 5 coupler provides a first means for tuning the output
- 6 wavelength of the laser.

7

- 8 Alternatively, the laser further comprises a pair of
- 9 Brewster plates and a cavity mirror mounted on a
- 10 piezoelectric crystal wherein the combined movement of:
- 11 the Brewster plates and the cavity mirror provide a
- 12 second means for tuning the output wavelength of the
- 13 laser.

14

- 15 According to a fourth aspect of the present invention
- 16 there is provided a scanning Vertical External Cavity
- 17 Surface Emitting Laser suitable for use in high
- 18 resolution spectroscopy experiments comprising apparatus
- 19 for selecting and stabilising the operating frequency of
- 20 the laser, apparatus for scanning the operating frequency
- 21 of the laser, a wafer structure and a heatspreader
- 22 located at an active surface of the wafer structure
- 23 wherein the heatspreader comprises a non-birefringent
- 24 material and an anti-reflection coating located on an
- 25 active surface of the heatspreader.

26

- 27 Preferably the apparatus for selecting and stabilising
- 28 the operating frequency of the laser comprises an
- 29 intracavity polarisation selecting element, an
- 30 intracavity etalon and an external reference cavity.

- 32 Preferably the apparatus for scanning the operating
- 33 frequency of the laser comprises a cavity mirror mounted

1.	ΟD	a	first	piezoelectric	crystal	and	aπ	output	coupler
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- 2 mounted on a second piezoelectric crystal wherein the
- 3 combined movement of the cavity mirror and the output
- 4 coupler provides a first means for tuning the output
- 5 wavelength of the laser.

6

- 7 Alternatively, the apparatus for scanning the operating
- 8 frequency of the laser comprises a pair of Brewster
- 9 plates and a cavity mirror mounted on a piezoelectric
- 10 crystal wherein the combined movement of the Brewster
- 11 plates and the cavity mirror provides a second means for
- 12 tuning the output wavelength of the laser.

13

- 14 Preferably the anti-reflection coating is optimised for
- 15 efficient operation with a refractive index of the non-
- 16 birefringent material...

17

- 18 Preferably the active surface of the heatspreader
- 19 comprise a wedge.

20

- 21 Most preferably the heatspreader comprises a single
- 22 diamond crystal.

23

- 24 Aspects and advantages of the present invention will
- 25 become apparent upon reading the following detailed
- 26 description and upon reference to the following drawings
- 27 in which:

- 29 Figure 1 presents a schematic representation of an
- 30 improved Vertical External Cavity Surface
- 31 Emitting Laser (VECSEL) that incorporates
- 32 intracavity elements for single frequency
- 33 selection;

2	Figure 2	presents:
3		(a) a schematic representation; and
4		(b) a schematic bandgap diagram,
5		of the gain medium of a 980 nm VECSEL of
6		Figure 1;
7		
8	Figure 3	presents further detail of the cooling
9		apparatus and a heatspreader employed by the
10		VECSEL of Figure 1;
ļl		
12	Figure 4	presents an output power curve, as a function
13		of pump power, for the VECSEL of Figure 1
14		designed to operate around a 980 nm central
15		output wavelength;
16		
17	Figure 5	presents a measured residual frequency noise
18		output for the 980 nm VECSEL of Figure 1; and
19	•	· · · · · · · · · · · · · · · · · · ·
20	Figure 6	presents a measured wavelength tuning curve for
21		the 980 nm VECSEL of Figure 1 when coupled to a
22		transmission peak of an external reference
23		cavity.
24	J	
25	Referring	to Figure 1 a schematic representation of a
26	Vertical	External Cavity Surface Emitting Laser (VECSEL)
27	1, in acc	ordance with an aspect of the present invention
28	is provid	ed. The VECSEL 1 can be seen to comprise a
29	wafer str	ucture 2 mounted within a cooling apparatus 3
30	that is	located within a three mirror folded cavity
31	arrangemen	nt.
32		

1 A first mirror within the cavity arrangement comprises a 2 Bragg reflector 4 associated with the wafer structure 2

3 (further details of which are outlined below). A second

4 mirror comprises a standard curved cavity mirror 5

5 mounted on a first piezoelectric crystal 6 so allowing

6 for fine adjustment of the length of the cavity. An

7 output coupler 7, mounted on a second piezoelectric

8 crystal 8 so allowing for coarse adjustment of the length

9 of the cavity, is then employed as the third cavity

10 mirror. Between the curved cavity mirror 5 and the

11 output coupler 7 are located a birefringent filter 9

12 employed to provide coarse frequency selection within the

13 cavity and a solid etalon 10 employed for fine frequency

14 selection of the operating wavelength. The wafer

15 structure 2 is optically pumped by initially coupling the

16 output of a pump laser source (not shown) into an optical -

17 fibre 11. Thereafter, the coupled pump laser output is

18 focussed via two input lens elements 12 onto the wafer

19 structure 2.

20

21 A schematic representation of the wafer structure 2 is

22 presented in Figure 2(a). The wafer structure 2 is grown

23 by a metal-organic chemical vapour deposition (MOCVD)

24 technique on a 2 inch (5.08 cm) 500 mm thick (001) GaAs

25 substrate 13. The wafer structure 2 comprises a lower

26 end single distributed Bragg reflector 4, a gain medium

27 14, a carrier confinement potential barrier 15 and an

28 oxidation prevention layer 16.

29

30 The Bragg reflector 4 comprises thirty pairs of AlAs-GaAs

31 quarter-wave layers that exhibit a total reflectivity

32 greater than 99.9% centred at 980 nm while the carrier

33 confinement potential barrier comprises a single

1 wavelength-thick Al<sub>0.3</sub>Ga<sub>0.7</sub>As layer. The oxidation

2 prevention layer comprises a thin Ino.48Gao.52P cap.

3

4 The gain medium 14 comprises twelve 6 nm thick In<sub>0.16</sub>GaAs

- 5 quantum wells equally spaced between half-wave
- 6 Alo.osGao.sAs/GaAsP structures that allow the VECSEL 1 to be
- 7 optically pumped at 808 nm while generating an output in
- 8 the range of 970 995 nm. (referred to below as the 980
- 9 nm VECSEL)

10

- 11 A schematic representation of the lasing mechanism is
- 12 presented in the bandgap diagram of Figure 2(b). The
- 13 pump field 17 is absorbed in the barrier regions and
- 14 carriers thereafter diffuse into the quantum wells so as
- 15 to produce the required population inversion for lasing
- 16 to take place.

17

- 18 Figure 3 presents further detail of the cooling apparatus
- 19 3 and heatspreader 18 employed in order to improve the
- 20 operating characteristics of the VECSEL 1. In particular
- 21 the cooling apparatus 3 comprises a standard
- 22 thermoelectric cooler 19 while the heat spreader 18
- 23 comprises a single diamond crystal that comprises an
- 24 external, wedged face 20. A high performance anti-
- 25 reflection coating is deposited on the surface of the
- 26 wedged face 20.

27

- 28 The single diamond crystal heatspreader 18 is bonded in
- 29 optical contact with the active surface of the wafer
- 30 structure 2. The wafer structure 2 and heatspreader 18
- 31 are then clamped on top of a layer of indium foil 21 onto
- 32 the thermoelectric cooler 19.



1.2

Single diamond crystal is suited to be employed as the heatspreader 18 since it exhibits comparable thermal 2 conductivity levels as Sapphire and Silicon Carbide. 3 Thus, the described arrangement allows the heatspreader 4 18 to immediately spread the heat associated with the 5 pump field 17 to the cooling apparatus 3 after it has propagated only a limited distance into the gain medium 14, so significantly increasing the efficiency of the 8 addition there are further 9 device. advantages of employing the single diamond crystal as the 10 heatspreader 18 over those described in the prior art. 11 These reside in the fact that the single diamond crystal 12 As such the presence of the 13 is non-birefringent. heatspreader 18 no longer interferes with polarisation 14 selecting properties of the birefringent filter 9 and so 15 there are no additional intracavity losses experienced on 16 the output of the VECSEL 1 as the laser is tuned (see 17 18 Figure 6 below).

19

The lack of birefringence within the heatspreader 18 also 20 21 allows for an optimised anti-reflection coating to be It is known to those 22 applied to the wedged surface 20. skilled in the art that in order to optimise an anti-23 reflection coating it is necessary that the refractive 24 index of the medium to which the coating is to be applied 25 is known to a high degree of accuracy. Therefore, if the 26 heatspreader 18 were to exhibit birefringence (as is the 27 case for Sapphire and Silicon Carbide) two effective 28 refractive indices would be present. A direct result of - 29 this is that the effective refractive index experienced 30 by a propagating optical field of a fixed polarisation 31 would be critically dependent on the orientation of the 32 heatspreader 18 within the VECSEL 1, restricting 33

1 alignment to a single orientation only. Practically this

2 would significantly complicate the already difficult

3 cavity alignment process.

4

5 However, this is not the case with the single diamond

6 crystal heatspreader 18 thus permitting the incorporation

7 of the anti-reflection coating. The anti-reflection

8 coating acts to significantly reduces the power

9 modulation effects, caused by the presence of the

10 intracavity heatspreader 18, experienced when the 980 nm

11 VECSEL is wavelength tuned (see Figure 6 below).

12

13 Figure 4 provide some typical operational characteristics

14 of the described VECSEL 1 systems in the absence of the

15 birefringent filter 9 and the solid etalon 10. In

16 particular Figure 4 presents the 980 nm VESCEL output,

17 power as a function of pump power, when the heatsink

18 temperature was maintained at  $10\,^{\circ}\text{C}$ . The pump power was

19 provided by a commercially available 200  $\mu m$  fibre coupled

20 laser that generated a 25 W pump field at 808 nm. A 2%

21 output coupler 7 was employed so producing a maximum

22 output power of 1.75 W in a TEMpo mode with 6.2 W of pump

23 power.

24

25 On introducing the birefringent filter 9, the solid

26 etalon 10 and a 1% output coupler 7 to the cavity it is

27 possible to stabilise the output frequency of the device

28 to the side of a transmission peak of an external

29 reference cavity (not shown). The operational

30 characteristics of the 980nm VECSEL are shown in

31 Figure 5. The VECSEL 1 can be seen to operate at a

32 single frequency exhibiting a residual frequency

1 fluctuation amounting to a linewidth of around 85 kHz

2 r.m.s.

3

- 4 first 6 and second piezoelectric Βv employing the
- 5 crystals 8 the curved cavity mirror 5 and the output
- coupler 7, respectively, can be translated so as to allow
- 7 for the tuning of the output wavelength of the VECSEL 1.
- 8 A typical tuning curve for the 980nm VECSEL is presented
- 9 in Figure 6. It should be noted that the modulation in
- 10 the output power can be seen to have been reduced to less
- than 5%. 11

12

- 13 An alternative means for tuning the laser cavity
- 14 comprises the introduction of a pair of Brewster plates
- 15 (not shown) into the laser cavity. When the orientation
- 16 of the Brewster plates are rotated in conjunction with
- 17 the translational movement of the curved cavity 5 mirror
- 18 mounted on the piezoelectric crystal 6 the output
- 19 wavelength of the laser can be scanned, as is known to
- 20 those skilled in the art.

. 21

- 22 will be apparent to those skilled in the
- 23 alternative gain medium 14 may be incorporated within the
- 24 VECSEL 1 in order to provide different
- 25 Furthermore, the VECSEL outlined wavelength ranges.
- above has been described in relation to a three mirror 26
- 27 folded cavity chosen for ease of engineering.
- 28 it will again be readily apparent to those skilled in the
- 29 art that alternative cavity arrangements may be employed
- 30 without departing from the scope of the invention.
- 31 example the laser cavity may be established between the
- 32 Bragg reflector 4 and a curved output coupler 7.

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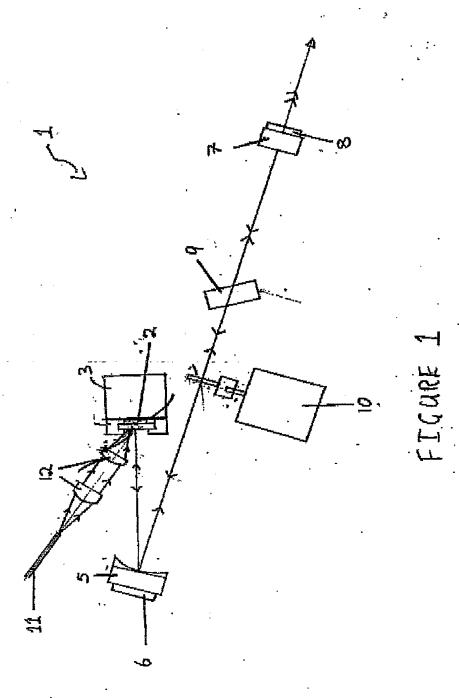
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The VECSEL described above employs a non-birefringent 1 heatspreader that allows the full tuning potential of the 2 associated gain medium to be exploited. Single diamond 3 crystal is employed as the heatspreader since it provides 4 the required level of thermal conductivity so as to act efficient heatspreader. fact that the The 6 heatspreader is non-birefringent means that there is no 7 detrimental interaction between the heatspreader and the 8 polarisation selecting properties of an intracavity 9 frequency · filter employed for coarse birefringent 10 selection within the cavity. Furthermore, the fact that 11 heatspreader is non-birefringent allows the application 12 of an optimised anti-refection coating to a wedged 13 surface of the heatspreader so as to significantly reduce. 14 the modulation on the output power experienced by prior 15 16 art systems.

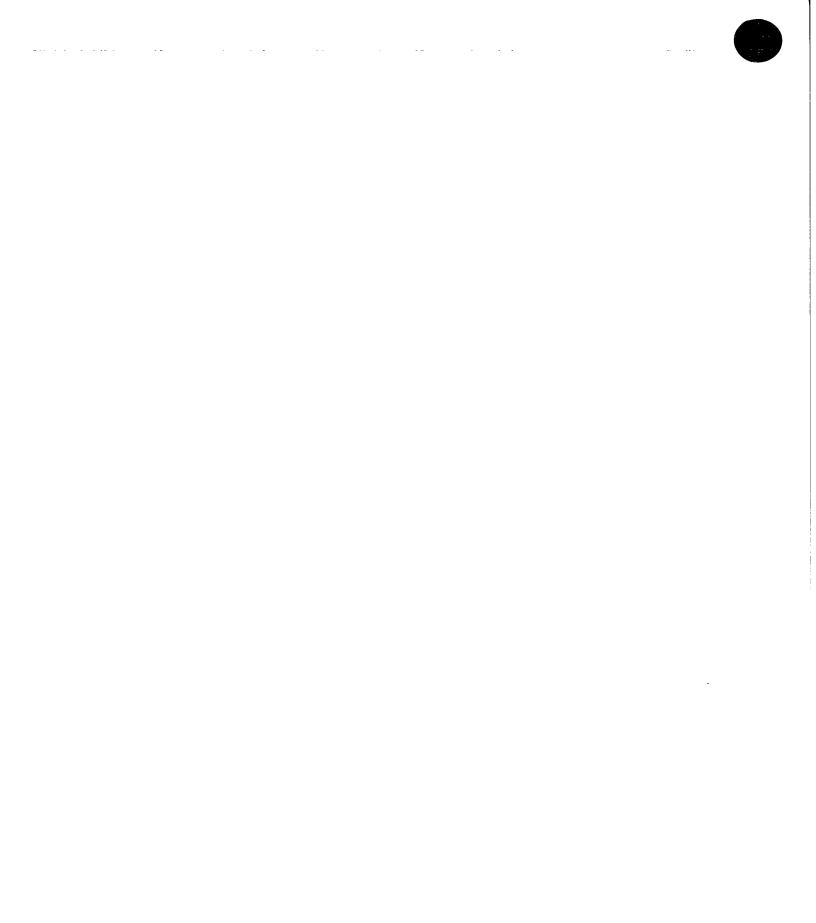
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foregoing description of the invention has been 18 presented for purposes of illustration and description 19 and is not intended to be exhaustive or to limit the 20 invention to the precise form disclosed. The described 21 embodiments were chosen and described in order to best 22 explain the principles of the invention and its practical 23 application to thereby enable others skilled in the art 24 to best utilise the invention in various embodiments and 25 modifications as suited the with various are 26 Therefore, further contemplated. particular use 27 modifications or improvements may be incorporated without 28 the invention departing from the scope of 29 intended. 30



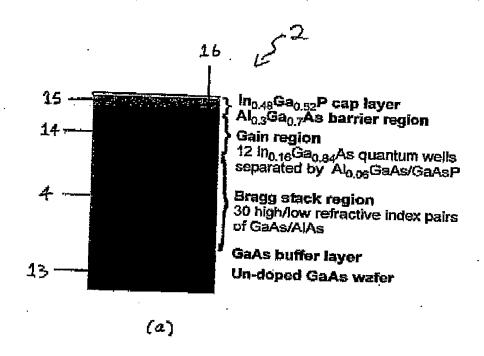


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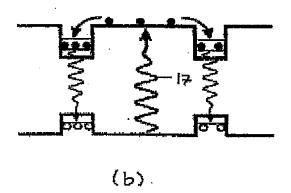


FIGURE 2



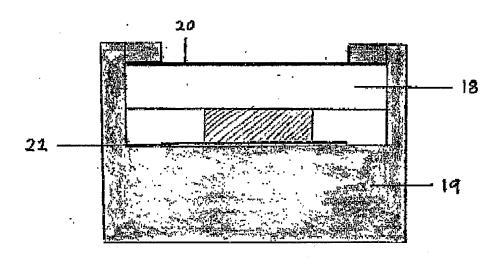


FIGURE 3



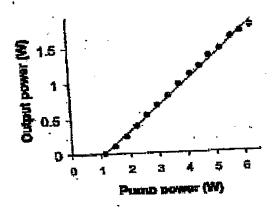


FIGURE 4

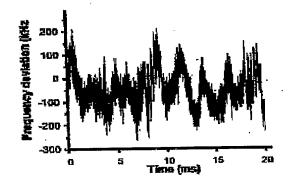


FIGURE 5



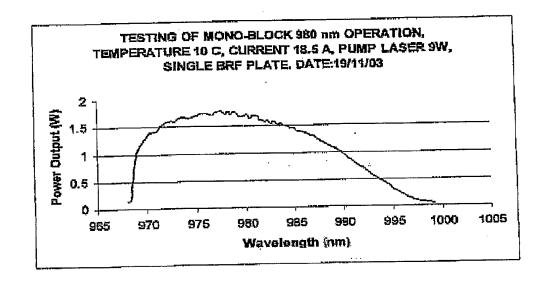


FIGURE 6

